







Call for Papers



The 2022 International Symposium on VLSI Technology Systems and Applications (VLSI-TSA) will be held on April 18-21, 2022 at the Ambassador Hotel, Hsinchu, Taiwan. The symposium has been kicked-off since 1983. It is a premiere conference in Taiwan and received up to 1,000 participants every year. It provides a unique opportunity to network with VLSI leading experts worldwide. Original and unpublished papers on all aspects of advanced VLSI technology and applications are solicited.

Hsinchu City: The well-known Taiwan's Silicon Valley is based with clusters of world-class high Tech. IC manufacturing and design. It is one-hour driving distance from Taipei, 40 minutes from the airport. Industry attendees may take this opportunity to visit Science Park business unit and academia attendees may visit major universities/institutes of Taiwan, either in Hsinchu, or down to the south by the high speed train within one hour.

COVID-19 Watch: 2022 VLSI-TSA is planned for an in-person/on-site event. In the meantime, we will keep Hybrid meeting (same as 2021) if COVID-19 still keeps a threat to the convention, i.e., arranging overseas presenters to provide a pre-recorded video for presentation on condition that they render into travel restrictions.

Paper submission click here

Papers in the following scope are solicited:

- Front-end CMOS and Foundry technology
- Standalone memory: DRAM, FLASH, emerging memory technology
- Ultra-low power CMOS and embedded memory
- Advanced process modules: e.g. gate stack, junction, strain/channel engineering, low-R contact, low-C spacer/ILD, interconnect technology, ALE and selective deposition, etc.
- Advanced packaging and 2.5D/3D Integration
- **TFT and organic electronics**
- MEMS, imagers and sensors
- Power and analog IC device and technology
- **Photonics and beyond CMOS Technology**
- RF & THz process, device and integration technology
- **Energy harvesting technology**
- Wearable and IoE enabling technologies
- Quantum phenomena and information technologies

- Nano-patterning: multiple patterning, directed selfassembly, EUV, etc.
- Advanced CMOS process and devices: Ge, SiGe, III-V,
 FinFET, GAAFET, low-dimensional materials and
 devices, 2D and nanowire devices
- BEOL compatible devices for 3D integration
- Material, Process and device modeling
- Reliability physics, characterization and test

- Neuromorphic devices and materials for braininspired computing
- Device/circuit technologies for AI deep learning applications
- Advanced manufacturing technology, metrology and yield

Paper Submission(s) Guideline:

- The paper should be written in English.
- Submissions of the <u>2-page camera-ready manuscript</u> in **pdf format**, including figures and tables.
- In addition to the camera-ready manuscript, the submission should include a 100~200 Word abstract.
- Upon acceptance of your paper, an electronic IEEE copyright form (eCF) is compulsory and must be submitted online via the Paper Submission site. For more information about IEEE Copyright, please refer to the IEEE Copyright Policy site.
- No-show papers will not be included in the symposium proceedings and will not be submitted to the IEEE Xplore database.
- All paper presenters are required to register for the symposium by February 28, 2022 and present at the symposium.

Important Dates:

- Paper Submission Deadline EXTENDED to November 10, 2021 23:59 (Taipei time)
- Acceptance Notification
 December 31, 2021
- Author Registration Deadline *February 28, 2022*

Student Subsidy:

<u>Financial support</u> for full-time overseas student authors is available.

Up to 65% discount for all students on registration fee.

Best Student Paper Award:

The selection will be based on the evaluation by members of technical committees of students' papers, as well as their oral presentations during the conference.

The Best Student Paper Award will be granted to the winning students at the next conference.

Late News Papers: (Submission Deadline: Jan 15, 2022)

A very limited number of high quality Late News Papers will be accepted.

<u>Late News Papers</u> are not eligible for the best student paper award.

For further information, please contact:

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Website: https://expo.itri.org.tw/2022vlsitsa





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